SPECTROSCOPIC ELLIPSOMETER

MODEL: M2000F by Woollam Co.

INSTALLATION PLACE: Plasma Laboratory, Department of Microelectronics

DESCRIPTION: The M2000-F Spectroscopic Ellipsometer system by J.A.WOOLLAM company may be used ex-situ or in-situ film characterization, and is equipped with a heating stage (home made) for thermal property measurements of polymer films (Glass transition temperatures).

SPECIFICATIONS
1. Samples larger than 1x1 mm
2. Maximum film thickness 10 μm
3. Wavelength range: 250nm – 900nm
4. Lamp Type and model : Xenon Lamp L2194-01
5. Angle of incidence: 75°
6. Software for data acquisition, data analysis and modeling

APPLICATIONS
1. Multi-layer thickness measurement
2. Refractive index and dielectric constant measurements of new thin-film materials
3. Film roughness estimation
4. In situ ellipsometry for real time thickness measurement. Mounting arms exist for attachment on Plasma Etching Reactor

CERTIFICATION/ACCREDITATION
This facility is not certified or accredited. Calibration standard for oxide thickness measurement exists

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